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High-energy x-ray photoelectron spectroscopy spectra of HfO₂ measured by Cr K α

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Note: This paper is part of the 2022 Special Topic Collection on Higher Energy X-ray Photoelectron Spectroscopy.

ABSTRACT

Hafnium oxide (HfO₂) grown by atomic layer deposition on Si was analyzed using high-resolution high-energy x-ray photoelectron spectroscopy (HAXPES). The HAXPES spectra of HfO₂ obtained using monochromatic Cr K α radiation at 5414.8 eV include two survey scans (Al K α and Cr K α) and high-resolution spectra of Hf 3s, Hf 3p_{3/2}, Hf 3d_{5/2}, Hf 4p_{3/2}, Hf 4d, Hf 4f, Hf 4s, and O 1s.

Key words: HfO₂, HAXPES, Cr K α

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Accession #:01739 and 01743

Technique: XPS

Host Material: HfO₂

Instrument: ULVAC-PHI Quantes

Major Elements in Spectra: Hf, O

Minor Elements in Spectra: None

Published Spectra: 10

Spectra in Electronic Record: 10

Spectral Category: Comparison

INTRODUCTION

While high-energy photoemission has been in use for decades, only very few reference spectra are available, even for common materials. The recent availability of performant lab-scale photoemission spectrometers (Refs. 1–3) requires reliable reference data.

In this work, we present reference spectra from hafnium oxide (HfO₂) grown by atomic layer deposition (ALD) on Si, which was analyzed using high-resolution high-energy x-ray photoelectron spectroscopy (HAXPES). The HAXPES spectra of HfO₂ obtained using monochromatic Cr K α radiation at 5414.8 eV include two survey scans (Al K α and Cr K α) and high-resolution spectra of Hf 3s, Hf 3p_{3/2}, Hf 3d_{5/2}, Hf 4p_{3/2}, Hf 4d, Hf 4f, Hf 4s, and O 1s.

SPECIMEN DESCRIPTION (ACCESSION # 01739)

Host Material: HfO₂

CAS Registry #: 12055-23-1

Host Material Characteristics: Homogeneous; solid; amorphous; dielectric; inorganic compound; thin film

Chemical Name: Hafnium oxide

Source: ALD grown

Host Composition: Hf, O

Form: Thin Film

Structure: Amorphous

History and Significance: Air exposed ALD HfO₂. The growth was performed using HfCl₄ and H₂O as precursors at 300 °C

As Received Condition: Piece of a 200 mm Si wafer

Analyzed Region: Same as host materials

Ex Situ Preparation/Mounting: Sample was taped on the sample holder using insulating removable 3M double sided tape.

In Situ Preparation: Before HAXPES measurement, the samples were cleaned with low energy Ar⁺ ions (100 eV). The cleaning procedure was stopped when the carbon level was reduced to a negligible level using Al K α radiation.

Charge Control: Low energy electrons (1 eV, filament 1.1 A) and low energy ions (10 eV, 5 mA emission)

Temp. During Analysis: 300 K

Pressure During Analysis: <5 × 10⁻⁷ Pa

Pre-analysis Beam Exposure: 0 s

SPECIMEN DESCRIPTION (ACCESSION # 01743)

Host Material: Au
CAS Registry #: 7440-57-5
Host Material Characteristics: Homogeneous; solid; amorphous; conductor; metal; other
Chemical Name: Gold
Source: 0.250 mm thick foil from Goodfellow, AU000372/5
Host Composition: Au
Form: Bulk
Structure: Amorphous
History and Significance: In-vacuum sputtered
As Received Condition: Foil
Analyzed Region: Same as host materials
Ex Situ Preparation/Mounting: The sample was taped on the sample holder using insulating removable 3M double sided tape.
In Situ Preparation: Sample was sputtered using 1 keV Ar⁺ ions until no C or O was observed.
Charge Control: Low energy electrons (1 eV, filament 1.1 A) and low energy ions (10 eV, 5 mA emission)
Temp. During Analysis: 300 K
Pressure During Analysis: 5×10^{-7} Pa
Pre-analysis Beam Exposure: 0 s

INSTRUMENT DESCRIPTION

Manufacturer and Model: ULVAC-PHI Quantes
Analyzer Type: Spherical sector
Detector: Multichannel resistive plate
Number of Detector Elements: 32

INSTRUMENT PARAMETERS COMMON TO ALL SPECTRA**Spectrometer**

Analyzer Mode: Constant pass energy
Throughput ($T = E^N$): The energy dependence can be modeled using the following equation: $A/E_p = (a^2/(a^2 + R^2))^b$, where a and b are constants, E_p is the pass energy, A is the peak area, and R is the retard ratio equal to E/E_p , where E is the kinetic energy. Three spectral regions [Ag 2s (3790–3830 eV), Ag 3s (700–740 eV), and Ag 3d (350–390 eV)] are recorded on a sputter-cleaned silver sample at different pass energies. The values of a and b are then determined to be 576.9 and 6.3, respectively, by a linear least square fit of the data applying the equation described above.

Excitation Source Window: Al
Excitation Source: Cr K α monochromatic
Source Energy: 5414.8 eV
Source Strength: 43 W
Source Beam Size: 100 × 100 μm^2
Signal Mode: Multichannel direct

Geometry

Incident Angle: 22°
Source-to-Analyzer Angle: 46°

Emission Angle: 45°
Specimen Azimuthal Angle: 0°
Acceptance Angle from Analyzer Axis: 0°
Analyzer Angular Acceptance Width: 20° × 20°

Ion Gun

Manufacturer and Model: ULVAC-PHI Quantes
Energy: 10 and 100 eV
Current: 5 mA
Current Measurement Method: Biased stage
Sputtering Species: Ar
Spot Size (unrastered): 10 000 μm
Raster Size: N/A
Incident Angle: 45°
Polar Angle: 45°
Azimuthal Angle: 45°
Comment: Gun used for neutralization

DATA ANALYSIS METHOD

Energy Scale Correction: Due to the too low intensity of the C 1s peak with Cr K α , and the presputtering of the sample, the binding energy was referenced by determining the binding energy position of the Hf 4d_{5/2} peak recorded by Al K α XPS measurement and subsequent correction shift of the C 1s peak to 284.8 eV. The determined binding energy position of Hf 4d_{5/2} is 213.14 eV. The binding energy shift of the Cr K α data was then performed by shifting the Hf 4d_{5/2} peak to 213.14 eV.

Recommended Energy Scale Shift: 0.86 eV for binding energy
Peak Shape and Background Method: Data treatment was performed using Shirley background and Gaussian–Lorentzian peak shapes.

Quantitation Method: Quantification was done using PHI MULTIPAK Software Version 9.9.0.8. The elemental relative sensitivity factors were derived according to ISO 18118 Equation (A.7): “The pure-element relative sensitivity factor (PERSF), Si(E_p), can be obtained from measurements of Si(ref) for the selected element and a measurement of the peak intensity for the selected key material, I (key), as given in Formula (A.7): Si(E_p) = (I(ref))/(I(key)).”

AUTHOR DECLARATIONS**Conflict of Interest**

The authors have no conflicts to disclose.

DATA AVAILABILITY

The data that support the findings of this study are available within the article and its supplementary material (Ref. 4).

REFERENCES

- ¹See: <https://www.ulvac-phi.com/en/products/xps/quantes/>.
- ²See: <https://www.kratos.com/products/axis-supra-xps-surface-analysis-instrument>.
- ³See: <https://scientaomicron.com/en/system-solutions/electron-spectroscopy/HAXPES-Lab>.
- ⁴See supplementary material at <https://doi.org/10.1116/6.0001530> for ASCII data of all shown spectra.

SPECTRAL FEATURES TABLE

Spectrum ID #	Element/ Transition	Peak Energy (eV)	Peak Width FWHM (eV)	Peak Area (eV × counts/s)	Sensitivity Factor	Concentration (at. %) ^a	Peak Assignment
01739-03	Hf 3s	2598.85	11.65	8180	1.552	42.6	HfO ₂
01739-03 ^b	Hf 3s satellite	2614.69	21.17	2852	HfO ₂
01739-04	Hf 3p _{3/2}	2107.41	6.37	24 315	4.794	42.5	HfO ₂
01739-05	Hf 3d _{5/2}	1661.91	2.29	35 593	8.342	42.8	HfO ₂
01739-06	Hf 4p _{3/2}	381.70	5.21	8389	1.783	43.7	HfO ₂
01739-07	Hf 4d _{5/2}	213.14	4.20	8812	1.695	50.5	HfO ₂
01739-07	Hf 4d _{3/2}	223.88	4.50	5906	1.119	50.5	HfO ₂
01739-08	Hf 4f _{7/2}	16.77	1.46	956	0.283	55.7	HfO ₂
01739-08	Hf 4f _{5/2}	18.42	1.46	713	0.212	55.7	HfO ₂
01739-08 ^b	O 2s	20.67	4.33	159	HfO ₂
01739-09	O 1s	530.27	1.72	2408	0.589	...	HfO ₂
01739-09	O 1s	531.79	1.72	285	0.589	...	Possible –OH
01739-09 ^b	Hf 4s	536.44	6.06	2048	HfO ₂

^aThe concentration is calculated by taking into account only the O 1s peak from HfO₂ and the Hf peak from the given transition.

^bNo experimental sensitivity factor available.

ANALYZER CALIBRATION TABLE^a

Spectrum ID #	Element/ Transition	Peak Energy (eV)	Peak Width FWHM (eV)	Peak Area (eV × counts/s)	Sensitivity Factor	Concentration (at. %)	Peak Assignment
01743-01	Au 3d _{5/2}	2206.8	2.59	47 379
01743-01	Au 4f _{7/2}	84.2	1.24	2 115
...	Cu 2p _{3/2}	932.9	1.34	7 090
...	Ag 2p _{3/2}	3352.7	2.61	30 352
...	Ag 3d _{5/2}	368.4	1.15	2978

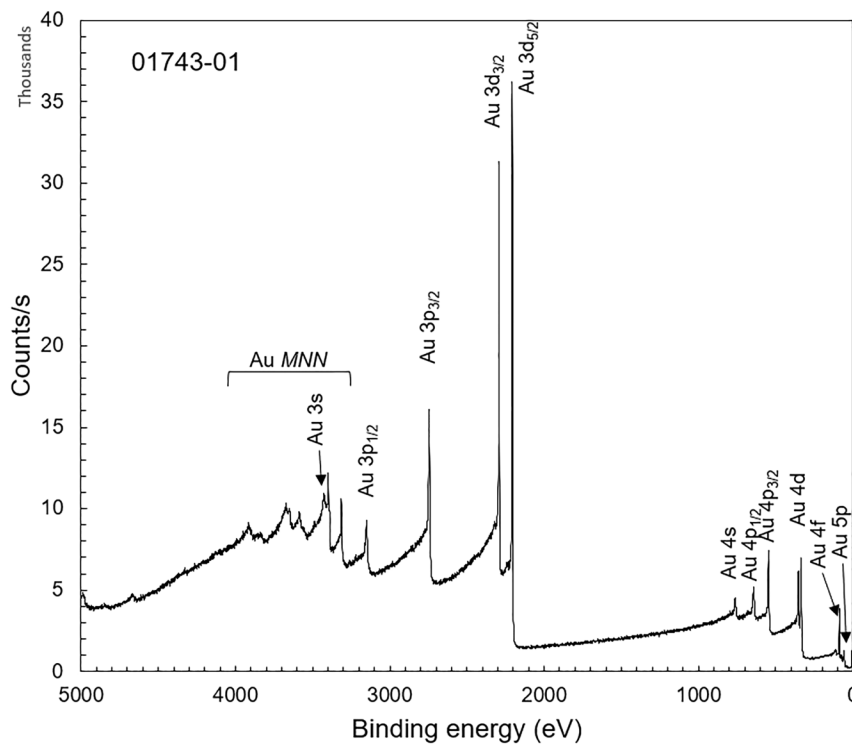
^aThe calibration table is established using the Cr K α photons and a pass energy of 112 eV corresponding to the presented high-resolution spectra.

GUIDE TO FIGURES

Spectrum (Accession) #	Spectral Region	Voltage Shift ^a (eV)	Multiplier	Baseline	Comment #
01743-01	Survey	0	1	0	Au spectrum with x-ray source Cr K α ^b
01739-01	Survey	0	1	0	X-ray source Al K α
01739-02	Survey	0	1	0	X-ray source Cr K α
01739-03	Hf 3s	–0.86	1	0	...
01739-04	Hf 3p _{3/2}	–0.86	1	0	...
01739-05	Hf 3d _{5/2}	–0.86	1	0	...
01739-06	Hf 4p _{3/2}	–0.86	1	0	...
01739-07	Hf 4d	–0.86	1	0	...
01739-08	Hf 4f	–0.86	1	0	...
01739-09	O 1s	–0.86	1	0	...

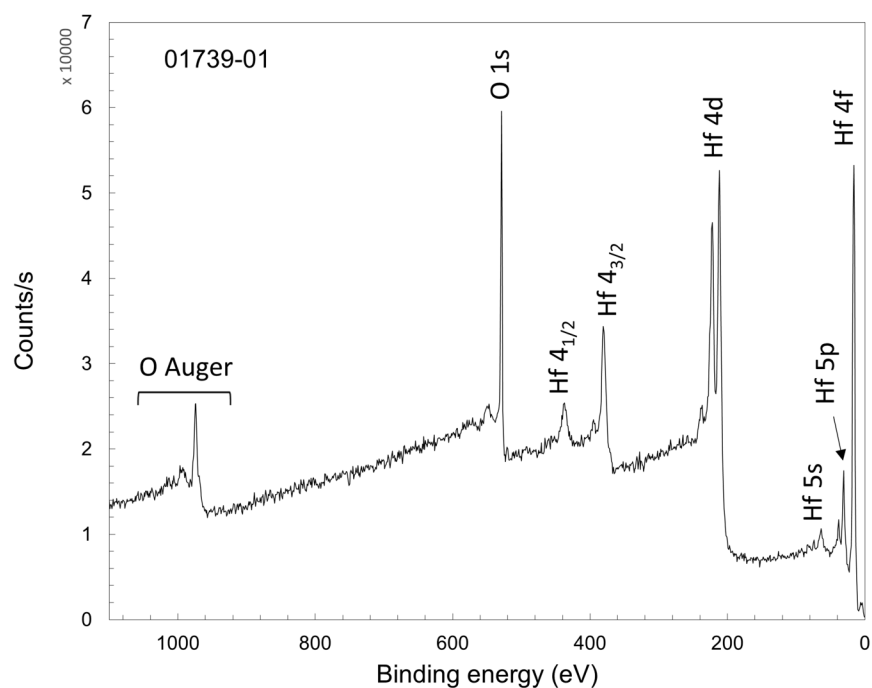
^aVoltage shift of the archived (as-measured) spectrum relative to the printed figure. The figure reflects the recommended energy scale correction due to a calibration correction, sample charging, flood gun, or other phenomenon.

^bThe reference spectrum included in this paper is the same as those included with other papers in this collection that use this x-ray source. This was intentional and not an error as submissions were requested to be accompanied by a wide-scan spectrum of sputter-cleaned gold taken on the same instrument and using the same settings as the wide-scan spectrum of the material or materials in the submission.



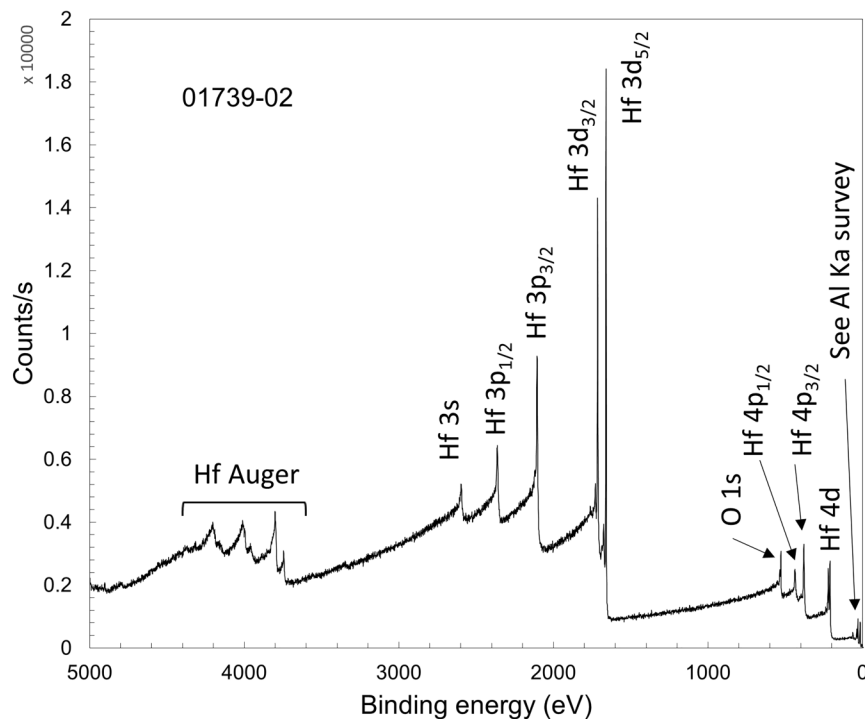
Accession #	01743-01
Host Material:	Au
Technique:	XPS
Spectral Region:	Survey
Instrument:	ULVAC-PHI Quantes
Excitation Source:	Cr K _α monochromatic
Source Energy:	8 eV
Source Strength:	9 W
Source Size:	0.1 × 0.1 mm ²
Analyzer Type:	Spherical sector analyzer
Incident Angle:	22°
Emission Angle:	45°
Analyzer Pass Energy:	280 eV
Analyzer Resolution:	1.9 eV
Total Signal Accumulation Time:	5210 s
Total Elapsed Time:	5700 s
Number of Scans:	1
Effective Detector Width:	31 eV

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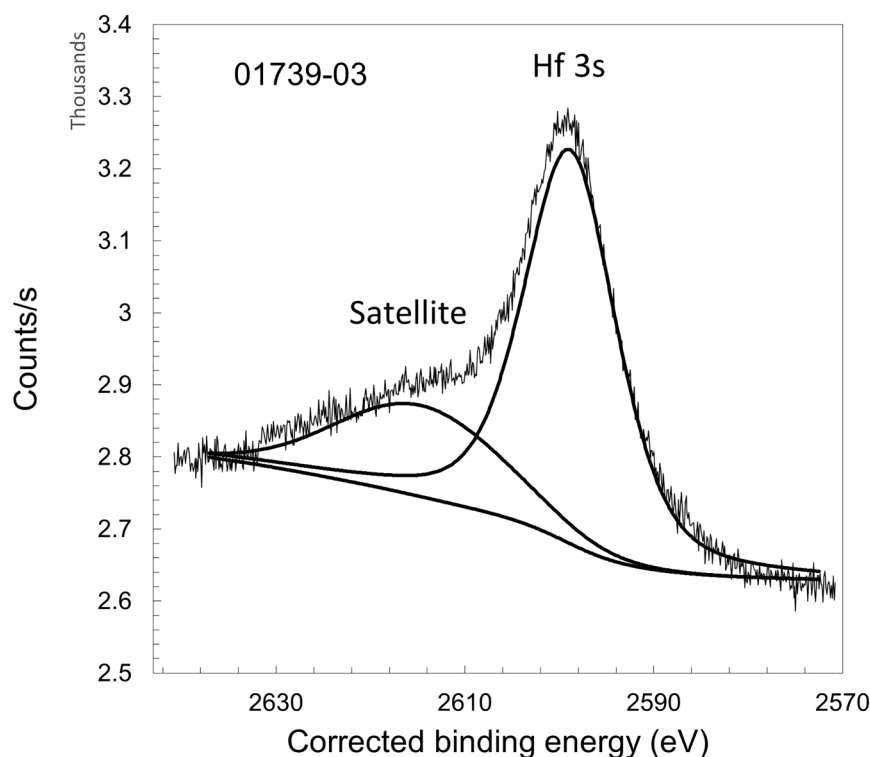
Accession #	01739-01
Host Material:	HfO ₂
Technique:	XPS
Spectral Region:	Survey
Instrument:	ULVAC-PHI Quantes
Excitation Source:	Al K _α monochromatic
Source Energy:	1486.6 eV
Source Strength:	25 W
Source Size:	0.1 × 0.1 mm ²
Analyzer Type:	Spherical sector analyzer
Incident Angle:	22°
Emission Angle:	45°
Analyzer Pass Energy:	280 eV
Analyzer Resolution:	1.9 eV
Total Signal Accumulation Time:	110 s
Total Elapsed Time:	130 s
Number of Scans:	1
Effective Detector Width:	31 eV

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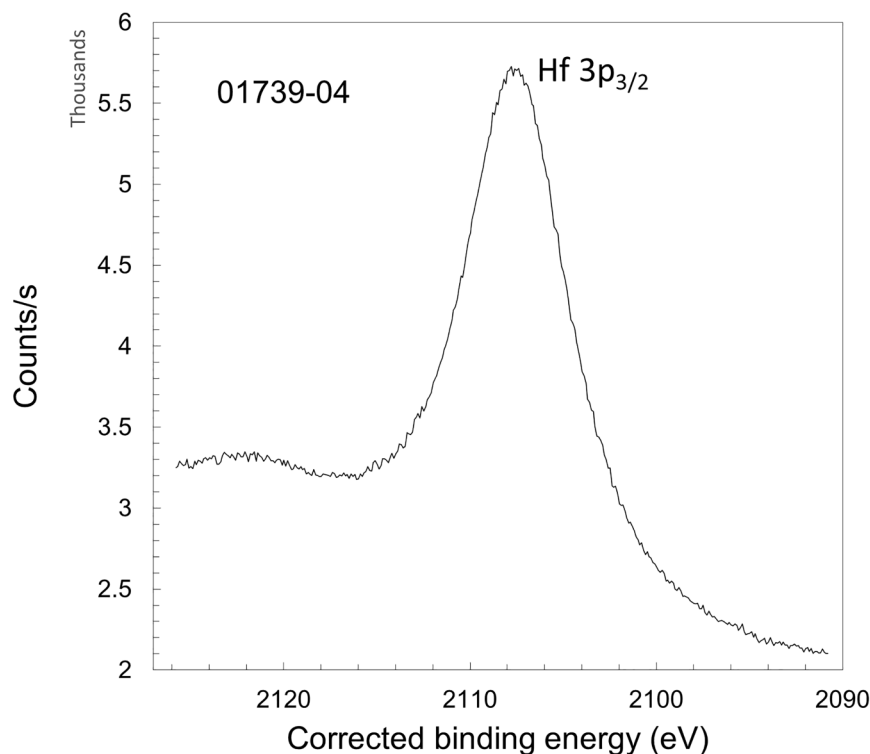
Accession #	01739-02
Host Material:	HfO ₂
Technique:	XPS
Spectral Region:	Survey
Instrument:	ULVAC-PHI Quantes
Excitation Source:	Cr K _α monochromatic
Source Energy:	5414.8 eV
Source Strength:	43 W
Source Size:	0.1 × 0.1 mm ²
Analyzer Type:	spherical sector analyzer
Incident Angle:	22°
Emission Angle:	45°
Analyzer Pass Energy:	280 eV
Analyzer Resolution:	1.9 eV
Total Signal Accumulation Time:	2500 s
Total Elapsed Time:	2750 s
Number of Scans:	10
Effective Detector Width:	31 eV

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- Accession #: 01739-03
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 3s

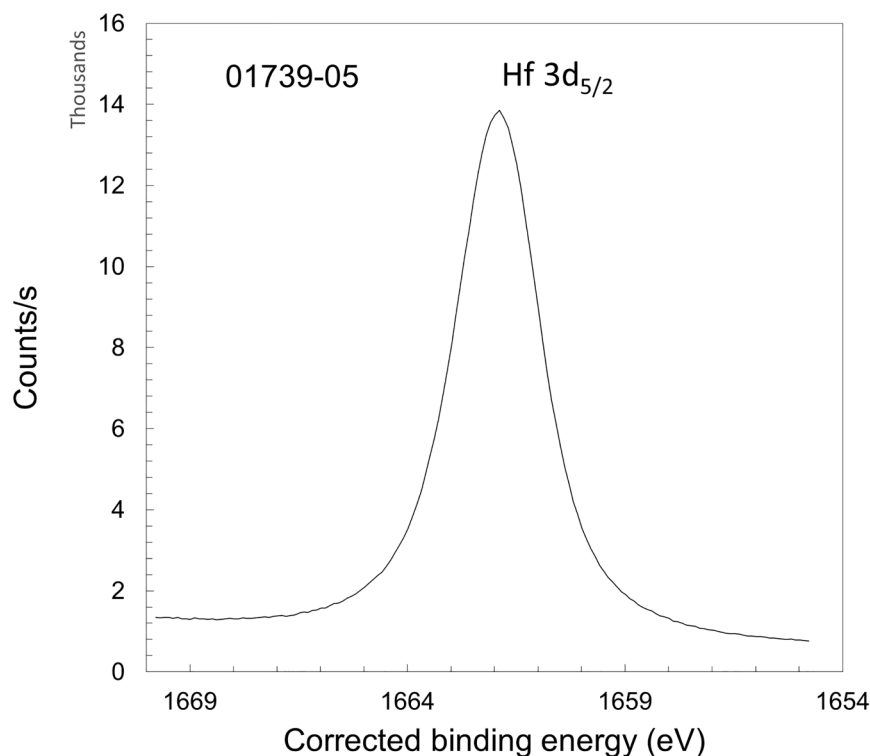
Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 11 200 s
 Total Elapsed Time: 12 300 s
 Number of Scans: 160
 Effective Detector Width: 12.4 eV



- Accession #: 01739-04
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 3p_{3/2}

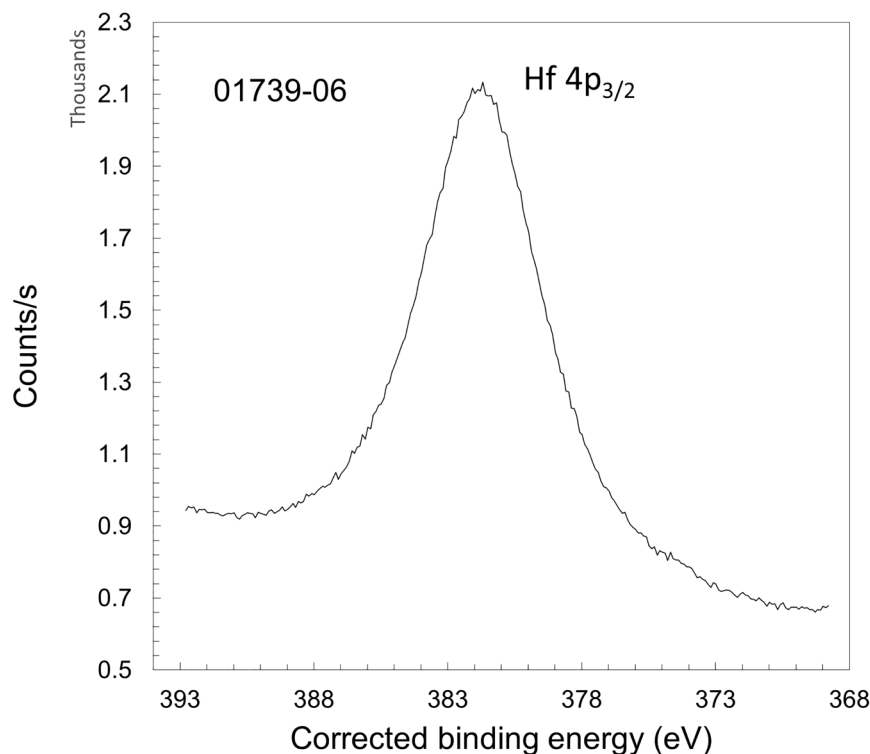
Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 3650 s
 Total Elapsed Time: 4015 s
 Number of Scans: 104
 Effective Detector Width: 12.4 eV

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- Accession #: [01739-05](#)
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 3d5/2

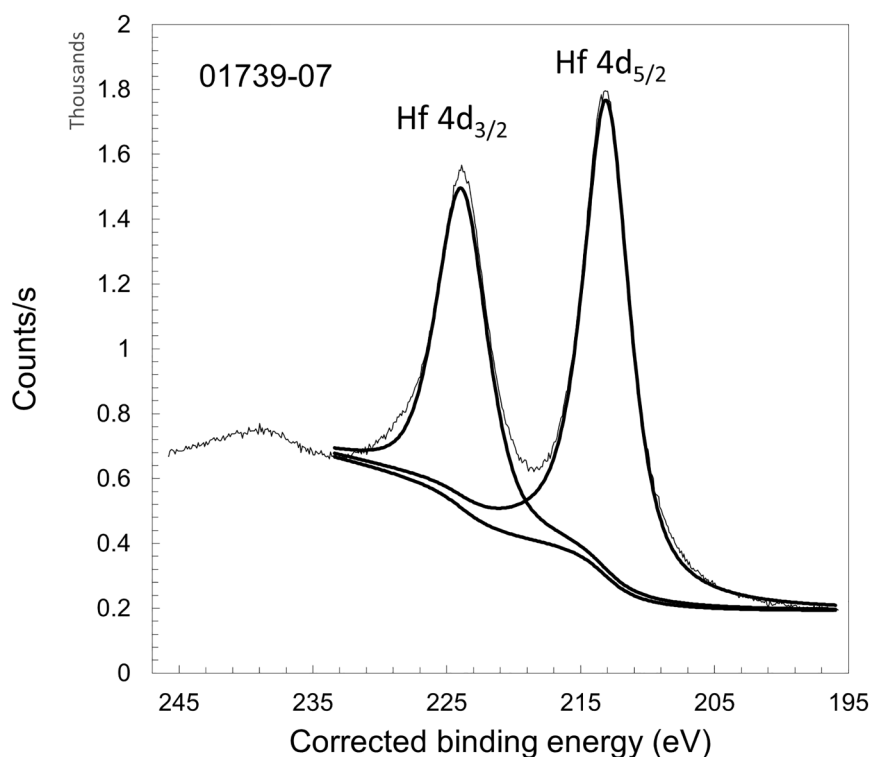
Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 2000 s
 Total Elapsed Time: 2200 s
 Number of Scans: 132
 Effective Detector Width: 12.4 eV



- Accession #: [01739-06](#)
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 4p3/2

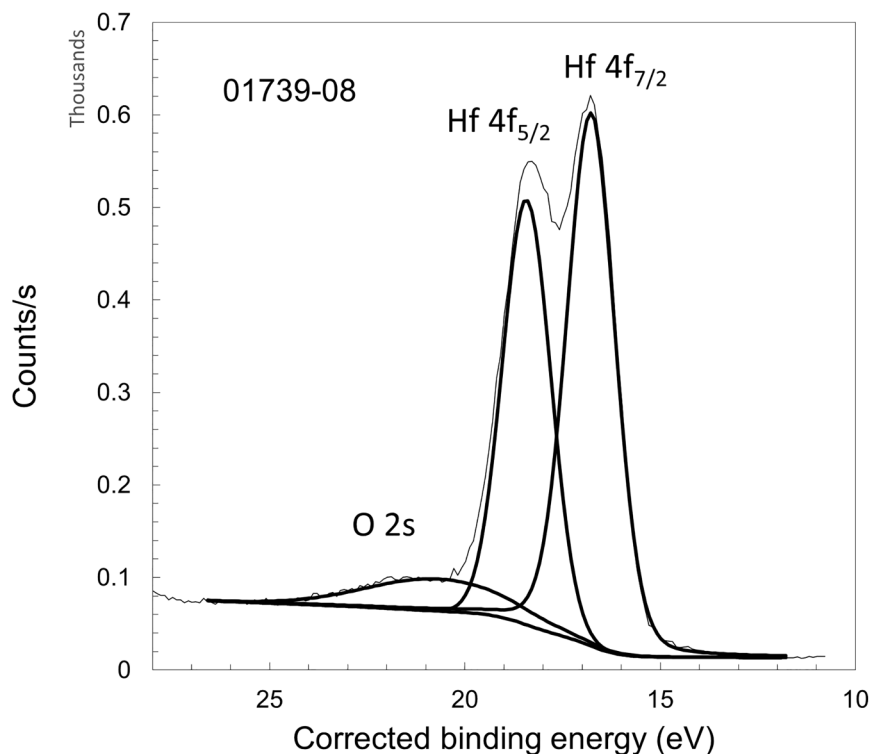
Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 4800 s
 Total Elapsed Time: 5300 s
 Number of Scans: 200
 Effective Detector Width: 12.4 eV

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- Accession #: 01739-07
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 4d

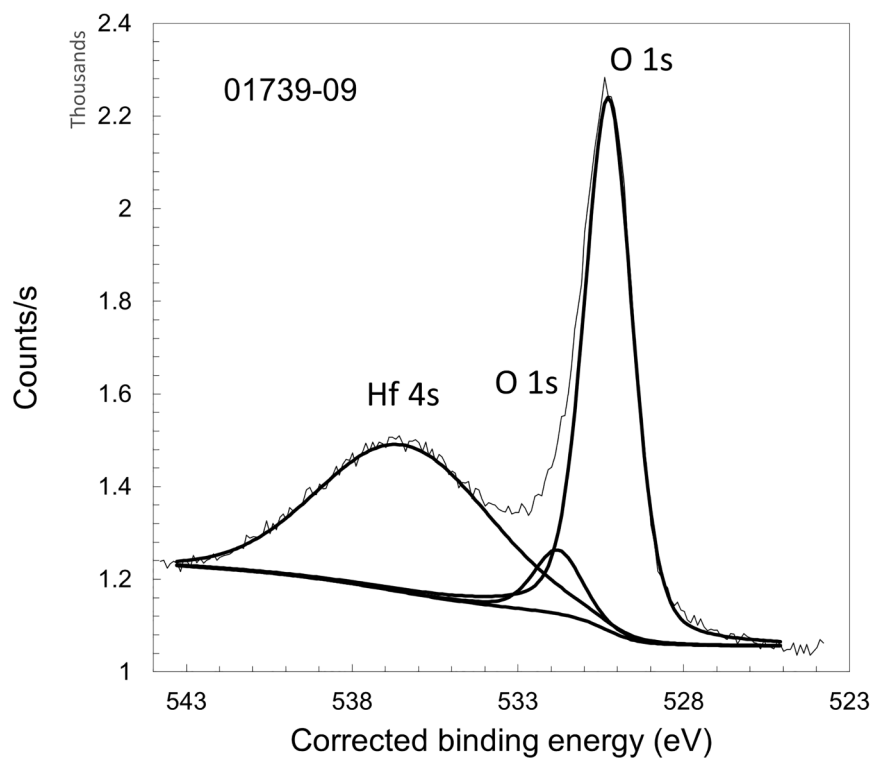
Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 6410 s
 Total Elapsed Time: 7050 s
 Number of Scans: 160
 Effective Detector Width: 12.4 eV



- Accession #: 1739-08
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: Hf 4f

Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 4020 s
 Total Elapsed Time: 4420 s
 Number of Scans: 200
 Effective Detector Width: 12.4 eV

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- Accession #: 01739-09
- Host Material: HfO₂
- Technique: XPS
- Spectral Region: O 1s

Instrument: ULVAC-PHI Quantes
 Excitation Source: Cr K_α monochromatic
 Source Energy: 5414.8 eV
 Source Strength: 52 W
 Source Size: 0.1 × 0.1 mm²
 Analyzer Type: Spherical sector
 Incident Angle: 22°
 Emission Angle: 45°
 Analyzer Pass Energy: 112 eV
 Analyzer Resolution: 0.86 eV
 Total Signal Accumulation Time: 2400 s
 Total Elapsed Time: 2650 s
 Number of Scans: 120
 Effective Detector Width: 12.4 eV

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